



IFW
PATENT

THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.: 10/706,862 Confirmation No.: 6724
Applicant(s): Ogihara et al.
Filed: November 12, 2003
Art Unit: 1711
Examiner: Irina S. Zemel
Title: COMPOSITION FOR FORMING POROUS FILM, POROUS FILM AND
METHOD FOR FORMING THE SAME, INTERLEVEL INSULATOR FILM,
AND SEMICONDUCTOR DEVICE

Docket No.: 035576/271443
Customer No.: 00826

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT
37 C.F.R. § 1.121

Sir:

In response to the Office Action dated November 22, 2004, please amend the above-identified application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims beginning on page 3 of this paper.

Remarks/Arguments begin on page 5 of this paper.